

Appl. No. : Unknown  
Filed : Herewith

## AMENDMENTS TO THE SPECIFICATION

**In the title, please amend the following:**

**POSITIVE TYPE RESIST COMPOSITION AND METHOD OF FORMING RESIST  
PATTERN FROM THE USING SAME**

**Immediately after the title of the specification on page 1, please insert the following paragraph:**

This application is the U.S. National Phase under 35. U.S.C. §371 of International Application PCT/JP2004/009455, filed June 28, 2004, which claims priority to Japanese Patent Application No. 2004-119498, filed April 14, 2004, and Japanese Patent Application No. 2003-189707, filed July 1, 2003. The International Application was published under PCT Article 21(2) in a language other than English.

**Please delete the following paragraph from page 1:**

~~Priority is claimed on Japanese Patent Application No. 2003-189707, filed July 1, 2003, and Japanese Patent Application No. 2004-119498, filed April 14, 2004, the contents of which are incorporated herein by reference.~~